

Tatsuya Yasuoka

List of Publications by Year in descending order

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papers

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docs citations

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#	ARTICLE	IF	CITATIONS
1	Bandgap engineering of $\hat{\Gamma}$ - $(\text{Al}_x\text{Ga}_{1-x})_2\text{O}_3$ by a mist chemical vapor deposition two-chamber system and verification of Vegard's Law. Applied Physics Letters, 2018, 113, .	3.3	64
2	$\hat{\Gamma}$ - $(\text{Al}_x\text{Ga}_{1-x})_2\text{O}_3$ single-layer and heterostructure buffers for the growth of conductive Sn-doped $\hat{\Gamma}$ -Ga ₂ O ₃ thin films via mist chemical vapor deposition. APL Materials, 2020, 8, .	5.1	15
3	Conductive Si-doped $\hat{\Gamma}$ - $(\text{Al}_x\text{Ga}_{1-x})_2\text{O}_3$ thin films with the bandgaps up to 6.22 eV. AIP Advances, 2020, 10, 115019.	1.3	13
4	Growth of $\hat{\Gamma}$ -Cr ₂ O ₃ single crystals by mist CVD using ammonium dichromate. Applied Physics Express, 2018, 11, 111101.	2.4	11
5	Optical Characterization of Gallium Oxide $\hat{\Gamma}$ and $\hat{\Gamma}^2$ Polymorph Thin-Films Grown on c-Plane Sapphire. Journal of Electronic Materials, 2021, 50, 2990-2998.	2.2	9
6	The effect of HCl on the $\hat{\Gamma}$ -Ga ₂ O ₃ thin films fabricated by third generation mist chemical vapor deposition. AIP Advances, 2021, 11, 045123.	1.3	7
7	Challenges of fabrication of a large-area-uniform molybdenum disulfide layered thin film at low growth temperature by atmospheric-pressure solution-based mist CVD. Japanese Journal of Applied Physics, 2018, 57, 110306.	1.5	6
8	Sub- $\hat{\Gamma}/4\text{m}$ features patterned with laser interference lithography for the epitaxial lateral overgrowth of $\hat{\Gamma}$ -Ga ₂ O ₃ via mist chemical vapor deposition. Applied Physics Letters, 2021, 119, 041902.	3.3	6